

CL Product Line

UV Excimer CLS-5000 laser series

Key features

- Very high beam position stability
- Very high beam pointing stability
- High repetition rate
- Magnetic switch generator
- Compact excimer laser
- Built-in Energy monitor
- Energy stabilization



CLS-5000 is a compact 193 nm compact excimer laser. It is also available in different configurations with 248 nm and 308 nm wavelengths. It has an outstanding beam stability performance because of its extra features in positioning and pointing, which makes CLS-5000 a great solution for a number of different applications. This short wavelength laser has high repetition rate, which is very important for material ablation processes optical projection lithography using photomasks. Magnetic switch generator and built-in energy monitor makes Optromix CLS-5000 very user friendly and convenient.

Applications

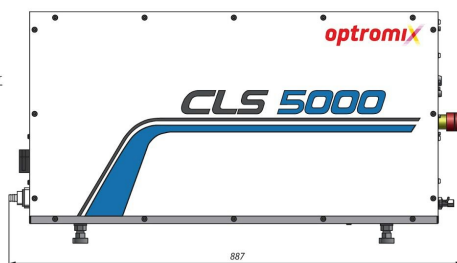
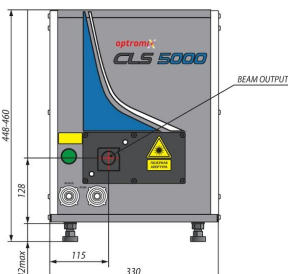
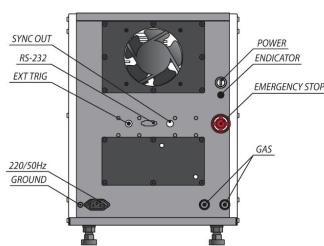
- Spectroscopy
- FBG writing
- Material processing
- Micromarking
- DUV Lithography



CLS-5000 series specification

Parameter	Value		
Gas mixture	ArF	KrF	XeCl
Wavelength	193 nm	248 nm	308 nm
Nominal Pulse Energy	15 mJ	25 mJ	12 mJ
Average Power	7.5 W	12.5 W	6 W
Max. repetition rate	500 Hz		
Pulse duration	11 ns	12 ns	
Pulse energy stability	sigma < 2%		
Beam size (V * H)	6 mm x 3.5 mm	6 mm x 4 mm	
Beam Divergence (V * H)	2 mrad x 1 mrad (stable resonator)		
Time jitter	< 2 ns		
Gas	1 premix cylinder		
Cooling	water < 1 liter/min		
Control interface	RS-232 (Windows)		
Power consumption	220 - 240 V, 50 - 60 Hz, 1 kW		
Dimensions (W x H x L)	336 x 454 x 887 mm		
Weight	85 kg		

Optromix provides 1 year warranty for all systems.



Information in this document is a subject to change without notice.